IN THE CLAIMS

- 1. (Cancelled)
- 2. (Currently Amended) The method of claim 1 claim 9, further comprising correcting and/or optimizing the mask and/or the simulation of image thereof.
- 3. (Original) The method of claim 2 wherein said correcting and/or optimizing comprises increasing or decreasing at least one magnitude or value of (a) an optical proximity correction factor and/or (b) a serif.
 - 4-6. (Cancelled)
- 7. (Currently Amended) The method of claim 6 claim 15, wherein correcting corner rounding effects comprises applying distortions are applied to corners and serifs in the mask.
 - 8. (Cancelled)
- 9. (Currently Amended) A method for producing a mask for fabrication of an integrated circuit, comprising:

simulating a mask from a first drawn layout, to produce a simulated mask; comparing the simulated mask and the first drawn layout; correcting the first drawn layout, to produce a second drawn layout; and producing a mask from the second drawn layout;

wherein the simulating comprises simulating proximity effects and resolution due to pixel spot size.

- 10. (Previously Presented) The method of claim 9, wherein the proximity effects comprise effects of light having a wavelength of approximately four times a feature size of said drawn layout.
- 11. (Previously Presented) The method of claim 9, further comprising simulating a photoresist pattern from the simulated mask, prior to correcting the first drawn layout.

12. (Previously Presented) A method of producing a semiconductor structure, comprising:

producing a mask by the method of claim 9; and producing a semiconductor structure from the mask.

13. (Previously Presented) A method of producing an integrated circuit, comprising:

producing a semiconductor structure by the method of claim 12; and producing a integrated circuit from the semiconductor structure.

- 14. (New) The method of claim 11, further comprising correcting and/or optimizing the simulation of the photoresist pattern.
- 15. (New) The method of claim 9, further comprising correcting corner rounding effects in an image produced by the mask.
- 16. (New) The method of claim 14, wherein said correcting and/or optimizing comprises increasing or decreasing at least one magnitude or value of (a) an optical proximity correction factor and/or (b) a serif.